

WHAT IS CLAIMED IS:

1. A wet substrate processing apparatus for processing a substrate, comprising:

- a table for holding a substrate; and
- a process liquid feeding mechanism for feeding process liquid to the substrate held on the table, wherein the table includes
 - a support face for supporting the substrate;
 - a first opening formed in the support face;
 - a second opening formed in the support face and arranged at least partially around the first opening;
 - a first fluid path configured to extend to the first opening of the support face through the table and be selectively connected to one of a gas feeding source, a liquid feeding source, and a vacuum source; and
 - a second fluid path configured to extend to the second opening of the support face through the table and open the second opening to the atmosphere.

2. The wet substrate processing apparatus according to claim 1, wherein the second fluid path extends through at least part of the table.

3. The wet substrate processing apparatus according to claim 2, wherein the table includes an expanded edge portion which extends in such a direction that a surface of the table expands; the second opening is located in the expanded edge portion; and the second fluid path extends through the expanded edge portion.

4. The wet substrate processing apparatus according to

claim 1, wherein a gas fed from the gas feeding source includes air or nitrogen, and a liquid fed from the liquid feeding source includes water.

5. The wet substrate processing apparatus according to claim 1, wherein the table is configured to be rotatable.

6. The wet substrate processing apparatus according to claim 1, including a polishing pad for polishing the substrate.

7. The wet substrate processing apparatus according to claim 1, wherein the first opening and the second opening are configured to be covered by the substrate when the substrate is held on the support face of the table.

8. The wet substrate processing apparatus according to claim 1, wherein the second opening is formed by one or a plurality of grooves arranged along an outer periphery of the support face, the one or plurality of grooves defining a ring shape as a whole.

9. A wet substrate processing apparatus for processing a substrate, comprising:

- a table for holding a substrate; and
- a process liquid feeding mechanism for feeding process liquid to the substrate held on the table, wherein the table includes
 - a support face for supporting the substrate;
 - a first opening formed in the support face;
 - a second opening formed in the support face and arranged at least partially around the first opening;
 - a first fluid path configured to extend to the first

opening of the support face through the table and be selectively connected to one of a gas feeding source, a liquid feeding source, and a vacuum source; and

a second fluid path configured to extend to the second opening of the support face through the table and be selectively connected to one of the gas feeding source, the liquid feeding source, and the vacuum source,

wherein the first opening and the second opening are configured to be covered by the substrate when the substrate is held on the support face of the table.

10. The wet substrate processing apparatus according to claim 9, wherein a gas fed from the gas feeding source includes air or nitrogen, and a liquid fed from the liquid feeding source includes water.

11. The wet substrate processing apparatus according to claim 9, wherein the table is configured to be rotatable.

12. The wet substrate processing apparatus according to claim 9, including a polishing pad for polishing the substrate.

13. The wet substrate processing apparatus according to claim 9, wherein the second opening is formed by one or a plurality of grooves arranged along an outer periphery of the support face, the one or plurality of grooves defining a ring shape as a whole.

14. A wet substrate processing apparatus for processing a substrate, comprising:

a table for holding a substrate; and

a process liquid feeding mechanism for feeding

process liquid to the substrate held on the table, wherein the table includes

- a support face for supporting the substrate;
- a first opening formed in the support face;
- a second opening formed in the support face and arranged at least partially around the first opening;
- a first fluid path configured to extend to the first opening of the support face through the table and be selectively connected to one of a gas feeding source, a liquid feeding source, and a vacuum source; and
- a second fluid path configured to extend to the second opening of the support face through the table and be selectively connected to one of the gas feeding source, the liquid feeding source, and the vacuum source,

wherein the second opening is formed by one or a plurality of grooves arranged along an outer periphery of the support face, the one or plurality of grooves defining a ring shape as a whole.

15. The wet substrate processing apparatus according to claim 14, wherein a gas fed from the gas feeding source includes air or nitrogen, and a liquid fed from the liquid feeding source includes water.

16. The wet substrate processing apparatus according to claim 14, wherein the table is configured to be rotatable.

17. The wet substrate processing apparatus according to claim 14, including a polishing pad for polishing the substrate.

18. The wet substrate processing apparatus according to claim 14, wherein the first opening and the second opening

are configured to be covered by the substrate when the substrate is held on the support face of the table.

19. A wet substrate processing apparatus for processing a substrate, comprising:

- a table for holding a substrate; and
- a process liquid feeding mechanism for feeding process liquid to the substrate held on the table, wherein the table includes
 - a support face for supporting the substrate;
 - a first opening formed in the support face;
 - a second opening formed in the support face and arranged at least partially around the first opening;
 - a first fluid path configured to extend to the first opening of the support face through the table and be selectively connected to one of a gas feeding source, a liquid feeding source, and a vacuum source; and
 - a second fluid path configured to extend to the second opening of the support face through the table and be selectively connected to one of the gas feeding source, the liquid feeding source, and the vacuum source,

wherein the first fluid path is configured to be connectable to the vacuum source.

20. A backing member configured to be mountable on a table for holding a substrate, the backing member including throughholes in positions which coincide with the first and second openings of the table of the wet substrate processing apparatus according to claim 1 when the backing member is mounted on the table.